

*Status of the Claims*

The listing of claims will replace all prior versions, and listings of claims in the application.

Claims 1-5 (Cancelled)

6. (Currently Amended) A maskless lithography system, comprising:

means for illuminating that generates light;

means for directing the light including a means for correcting aberrations in the light;

means for patterning the light after it is received from the means for directing, the means for patterning the light having a non-linear patterning surface; and  
means for exposing an object with the patterned light.

Claims 7-12 (Cancelled)

13. (New) A system, comprising:

an illumination system that supplies a beam of radiation;

a spatial light modulator that patterns the beam, the spatial light modulator including,

a non-linear substrate, and

an array of individually controllable elements coupled to the non-linear substrate;

a projection system that projects the patterned beam onto a substrate;

a directing device that directs the beam onto the spatial light modulator and the patterned beam onto the projection system; and

a focusing optical element that focuses the beam from the directing device onto the spatial light modulator, wherein a radius of the focusing element is substantially smaller than a radius of the spatial light modulator.

14. (new) The system of claim 13, wherein a chief ray of the beam impinges each element in the array of individually controllable elements normal to a surface of each of the elements.

15. (new) The system of claim 13, wherein the directing device comprises a means for correcting aberrations in the beam.

16. (new) The system of claim 13, wherein the non-linear substrate has a curved shape.

17. (new) The system of claim 13, wherein the non-linear substrate has a concave shape.

18. (new) The system of claim 13, wherein the non-linear substrate has a spherical shape.